Title (en)

PLASMA AND ION SOURCE

Publication

EP 0028303 B1 19831207 (DE)

Application

EP 80105360 A 19800908

Priority

DE 2944467 A 19791103

Abstract (en)

[origin: EP0028303A2] 1. Plasma and ion source generating in a limited volume on the basis of the electron cyclotron resonance a plasma by means of a magnetic field, the irradiation of microwaves and the supply of the gas to be ionized, with the use of a permanent magnet (1) provided with an axial bore (2) into which both the microwaves (3) and the gas (4) can be introduced.

IPC 1-7

H01J 27/18; H05H 1/50

IPC 8 full level

H01J 27/18 (2006.01); **H05H 1/50** (2006.01)

CPC (source: EP)

H01J 27/18 (2013.01)

Cited by

US4745337A; US5208512A; EP0326824A3; US4987346A

Designated contracting state (EPC)

DE FR GB NL

DOCDB simple family (publication)

EP 0028303 A2 19810513; **EP 0028303 A3 19810805**; **EP 0028303 B1 19831207**; DE 2944467 A1 19810514; DE 3065834 D1 19840112

DOCDB simple family (application)

EP 80105360 A 19800908; DE 2944467 A 19791103; DE 3065834 T 19800908